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## TABLE OF CONTENTS

Meeting the Maskmaking Challenge: A Technique to Achieve Rapid Reticle Writing Independent of Address Size Paul Warkentin, ATEQ Corporation. . . . .	1
Performance of a Variable Shape, Vector Scan E-Beam Lithography System for MaskMaking N. Goto and T. Uasa, JEOL Ltd. Michael Hassel-Shearer, JEOL U.S.A. Inc. . . . .	13
A High Accuracy Reticle Process Technology Kazumas Shigematsu, Takao Furukawa and Kimio Yanagida, Fujitsu, Ltd . . . . .	47
Microelectronic Engineering at Rochester Institute of Technology: Curriculum and Research Activity Overview Michael Jackson, Robert pearson and Lynn Fuller, Rochester Institute of Technology. . . . .	55
New High Sensitive Electron Beam Resist "EBR-9 HS30" Mutsua Kataoka, Toray Industries, Inc. . . . .	71
Data Compaction for Database Inspection William Robertson, KLA Instruments Corp. . . . .	101
GMC: A Negative Acting Resist Used in the Fabrication of Chromium Photomask A.E. Novembre, L.M. Kowalski, J. Fracjoviak, D.A. Mixon, and L.F. Thompson, AT&T Bell Laboratories . . . . .	135
Virtual Addressing Wayne Ruch, Harris Semiconductor . . . . .	153
A Mask Post Processing Management Syste Thomas Reeves, Karen Edwards, James Gibbons, Willard Mahoney, Steve Rexford and Bruce Roy, IBM Corporation . . . . .	169
A Perspective on Maskmaking for 1988 Thomas Halloran, Micrion Corporation . . . . .	199